





BEFORE AFTER

VACUUM CHAMBER PM TECHNIQUE ALCATEL COMPTECH 2460 PROCESS CHAMBER

OBJECTIVE:

TO PM THE ALCATEL COMPTECH 2460 PROCESS CHAMBER IN AN EFFECTIVE AND TIMELY MANNER, WHILE IMPROVING TOOL RECOVERY AND PARTICLE PERFORMANCE

NOTE: THE TOOL THAT WAS PM'D HAD NEVER HAD ALL OF THE DEPOSITION REMOVED. IN ORDER TO KEEP THE CHAMBER IN OPTIMUM CONDITION A REGULARLY SCHEDULED CHAMBER PM IS RECOMMENDED

<u>Vacuum Chamber</u>: ALCATEL COMPTECH 2460

Vacuum Chamber Process Residue: PROCESS INDUCED RESIDUE (AL₂O₃)

Vacuum Chamber Components: PROCESS CHAMBER

Old Procedure: Scrape/vacuum out excess build-up deposition

(NOT ENTIRELY REMOVED)
Recovery time: 12 to 16 hours

New Procedure: 3 hours using 140D/280D ScrubPADS, UltraSOLV® Sponge,

and MiraWIPES®

Recovery time: TBD

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Vacuum Chamber Products:

Note: Products used for initial clean. Once regular PM cycle is developed, products may change

- (3) <u>HT4514D</u>-10-1 140 Grit Diamond ScrubPAD
- (1) HT4528D-10-1 280 Grit Diamond ScrubPAD
- (1) HT4754 UltraSOLV® Sponge
- (3) HT5790S-5 MiraWIPES®



View "How to" instructional videos on http://www.foamtecintlwcc.com/flash/

- **Step 1:** Using proper procedures and **safety guidelines**, shutdown and prepare Alcatel 2460 Process Chamber for wet clean
- **Step 2:** Fill FT1301 plastic container with approximately 12oz of DI water and place next to process chamber (See Fig 1)



Fig 1: FT1301 plastic container with DI water

Step 3: Place <u>HT4514D</u> 140 Grit Diamond ScrubPAD and <u>HT4754</u> UltraSOLV[®] Sponge in container of DI water to moisten products (See Fig 2)

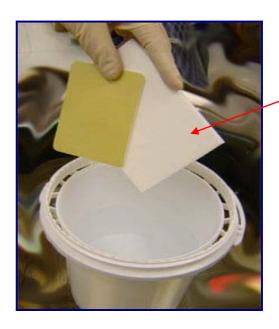


Fig 2: Place Diamond ScrubPAD and UltraSOLV® Sponge in container of DI water

- **Step 4:** Take **lightly dampened** UltraSOLV[®] Sponge and wipe area of process chamber that is to be cleaned in order to remove flaking deposition from chamber
- **Step 5:** Take **lightly dampened** 140 Grit Diamond ScrubPAD and scrub a small area of the process chamber (See Fig 3)

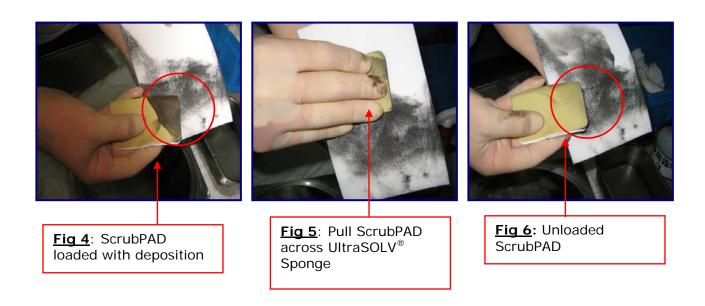
Fig 3: Scrubbing process chamber with Diamond ScrubPAD



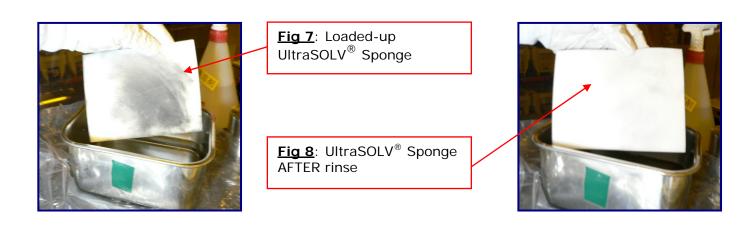
NOTE: REMEMBER IT IS NOT NECESSARY TO USE A LOT OF DI WATER DURING THIS SCRUB PORTION OF THE PM, ONLY ENOUGH TO KEEP DIAMOND ScrubPAD MOIST

Step 6: After scrubbing a small area with the 140 Grit Diamond ScrubPAD, take the lightly dampened UltraSOLV® Sponge and wipe deposition from the scrubbed area

Step 7: As Diamond ScrubPAD loads-up with deposition, pull ScrubPAD across damp UltraSOLV® Sponge to properly unload (See Fig 4, 5 & 6)



Step 8: Unload UltraSOLV® as much as possible by placing it in container of DI water and RINSE-OUT thoroughly (See Fig 7 & 8)



- **Step 9:** As the <u>HT4514D</u> 140 Grit Diamond ScrubPAD becomes worn, replace with a second 140 Grit Diamond ScrubPAD
- **Step 10:** Repeat steps 4 9 for all remaining areas throughout process chamber. Remember to unload ScrubPAD and UltraSOLV® Sponge as necessary

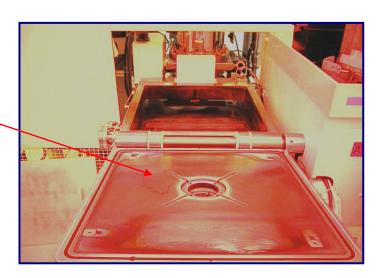
Step 11: Carefully clean chamber wall area near electrode with ScrubPAD (See Fig 9)

Fig 9: Area on chamber wall near electrode



- **Step 12:** Place <u>HT4528D</u> 280 Grit Diamond ScrubPAD in container of DI water to moisten product
- **Step 13:** Take **lightly dampened** 280 Grit Diamond ScrubPAD and scrub a small area of the chamber lid (See Fig 10)

<u>Fig 10</u>: Scrub chamber lid with 280 Grit Diamond ScrubPAD



- Step 14: After scrubbing a small area with the 280 Grit Diamond ScrubPAD use the lightly dampened UltraSOLV® Sponge to wipe deposition from the scrubbed area
- Step 15: As ScrubPAD loads-up with deposition, pull ScrubPAD across damp UltraSOLV® Sponge to properly unload (See Step 7 and Step 8)
- Continue scrub-wipe-unload procedure until all process residue is removed from **Step 16:** chamber lid (See Fig 11)

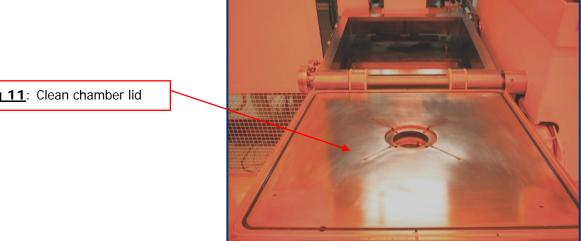


Fig 11: Clean chamber lid

When scrub portion of wet clean is complete, prepare chamber for FINAL WIPE **Step 17:** PROCEDURE by rinsing out UltraSOLV® Sponge with fresh DI water and performing a complete final process chamber wipe using the dampened UltraSOLV® Sponge

FINAL WIPE PROCEDURE:

IMPORTANT NOTE

THE USE OF <u>HT5790S</u> MIRAWIPES DURING FINAL WIPE PORTION OF PROCEDURE IS A CRITICAL STEP TO EFFECTIVELY REMOVING <u>PARTICLE DEFECTS</u> FROM ALCATEL COMPTECH 2460 PROCESS CHAMBER

NOTE:

Figure below shows how much more deposition the Foamtec International MiraWIPE® can remove from a critical surface compared to the standard fab wiper, making the MiraWIPE® FINAL WIPE PROCEDURE the most **CRITICAL STEP** of the PM procedure (See Fig 12a & 12b)

<u>Fig 12a</u>: Current fab wiper after completely wiping process chamber

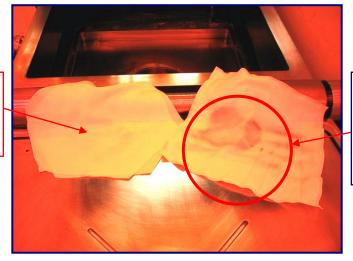


Fig 12b: Particles picked up using HT5790S MiraWIPES® after completely wiping with current fab wiper

MiraWIPES® are the <u>KEY STEP</u> for <u>DEFECT</u>
REDUCTION and <u>IMPROVED TOOL RECOVERY</u>

- **Step 18:** After scrubbing Alcatel 2460 Process Chamber remove and replace your gloves with a clean pair
- **Step 19:** If available, use clean dry N_2 to blow out the small areas and tight corners where DI water may have accumulated during the wet clean

Step 20: Fold the <u>HT5790S</u> MiraWIPE® into quarters and dampen with IPA

Step 21: With the dampened MiraWIPE® wipe down all areas of the process chamber, ensuring to refold the MiraWIPE® as necessary to expose a clean side of the MiraWIPE® as you wipe all areas within the chamber

NOTE: Replace with a new IPA dampened MiraWIPE® as necessary

Step 22: Repeat above MiraWIPE® FINAL WIPE PROCEDURE on all remaining areas of the process chamber and associated parts

Step 23: Using proper procedures and **safety guidelines** and return Alcatel 2460 Process Chamber back to production